Atmospheric-Pressure Remote Plasma Processing Equipment

Low-temperature treatment & electrical field shielding structure prevents damage

Features & Equipment specifications

1» No damage
Low-temperature treatment & electrical field shielding structure prevents heat and electrical damage

2» Advanced treatment performance
High-speed (10 m/min) treatment at 10° or under (treats glass substrates for LCD)

3» Extensive lineup
Handles widths from 160 to 3400 mm

4» Extensive and proven results
Adopted in LCD plants and numerous other production processes

Widths handled
160 to 3400 mm

Utility
Power, Treatment gas (N2, CDA), Exhaust, Cooling water
### Applications

<table>
<thead>
<tr>
<th>Field</th>
<th>Usage</th>
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<tbody>
<tr>
<td>LCD</td>
<td>Increases the wettability of glass surfaces, improves the wet cleaning effect</td>
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<td>Touch panels, OLED, etc.</td>
<td>Reforms the surface of conductive film, pretreatment for bonding</td>
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</tbody>
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#### Basic treatment performance

- **Contact angle data of glass substrate (dependence on conveying speed)**

  [Diagram showing contact angle data with зависимости от скорости подачи]

- **Relation between conveying speed and changes in the substrate temperature**

  [Diagram showing relationship between conveying speed and substrate temperature]

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